

**RESPONSE UNDER 37 CFR 1.116
EXPEDITED PROCEDURE
EXAMINING GROUP 1794
Docket No.: 0001.1045**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of:

Joo-Ho KIM et al.

Application No. 10/529,044

Group Art Unit: 1794

Confirmation No. 1715

Filed: January 17, 2006

Examiner: Kevin M. Bernatz

For: HIGH DENSITY RECORDING MEDIUM WITH SUPER-RESOLUTION NEAR-FIELD
STRUCTURE MANUFACTURED USING HIGH-MELTING POINT METAL OXIDE OR
SILICON OXIDE MASK LAYER

AMENDMENT AFTER FINAL REJECTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Attention: **BOX AF**

Sir:

This is in response to the Advisory Action issued July 29, 2009 and to the Final Office Action mailed May 19, 2009, having a period for response set to expire on August 19, 2009.

The following amendments and remarks are respectfully submitted. Reconsideration of the claims is respectfully requested.